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Appl No.: 10/665,339

AUG 01 2007

Atty. Dkt. UCF-397CIP

REMARKS/ARGUMENTS

Favorable consideration of this application is respectfully requested. Applicant has amended claims 1, 5-9, 13, 15, 18-19 and 23 and cancelled claim 2. Applicant believes that the amendments place the claims in condition for allowance. Favorable reconsideration of this application is, consequently, earnestly solicited in view of the following remarks.

Applicant thanks Examiner Angebrannt for the telephone interview in December to discuss the advisory action conclusion that Applicant lost "continuity". After it was brought to the Examiner's attention that the original patent application was filed as a continuation-in-part of co-pending patent application serial number 09/750,708 filed December 28, 2000 now U.S. Patent No. 6,673,497, Examiner agreed that the subject application does in fact have continuity with the parent application.

35 U.S.C. 112 Rejections:

Claims 1-25 were rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the written description requirement.

Claims 1, 5-9, 13, 15, 18-19 and 23 have been amended per our telephone interview on May 30, 2007. Our understanding is that the section 112 rejection is no longer applicable. Thus removal of the rejection is respectfully requested.

35 U.S.C. 103(a) Rejections:

Claims 13 and 23-24 were rejected under 35 U.S.C. 103(a) as being unpatentable over Araujo et al. in view of Bukharev, Efimov, Blackwell and Borelli. Applicant has amended claims 13, 15, 18-19 and 23 to clarify the subject matter Applicant regards as the invention including the limitations of exposing the UV exposed PTR glass blank containing precursors of nucleation centers with the high intensity visible light to decrease concentration of the precursors to decrease the rate of crystallization at the development stage to increase a refractive index in the PTR glass after exposure to the visible light to record the hologram, wherein the visible light exposure of the UV exposed PTR glass blank causing a nonlinear transformation of nucleation centers and thermal treating the PTR glass exposed to both the UV and visible radiation to provide phase transformation depending on an amount and

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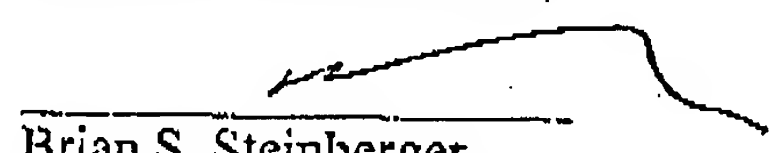
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intensity of visible radiation to allow crystal growth in the UV exposed area using a nonlinear mechanism for destruction of nucleation centers in the area exposed to visible light. Applicant believes that amended claim 13 and 23-24 are allowable over Araujo et al. in view of Bukharev, Efimov, Blackwell and Borelli. Thus removal of the rejection is requested.

Claims 1, 3-13 and 23-24 were rejected under 35 U.S.C. 103(a) as being unpatentable over Araujo et al. in view of Bukharev, Effimov, Blackwell and Borelli and further in view of Gaissinsky and claims 1 and 3-25 were rejected under 35 U.S.C. 103(a) as being unpatentable over Araujo et al. in view of Bukharev, Effimov, Blackwell, Borelli and Gaissinsky and further in view of IBM Tech. Disclosure. For the reasons provided above, Applicant believes that claims 1 and 3-25, as amended are allowable under section 103(a) over the cited prior art and respectfully requests removal of the rejection.

In view of the foregoing considerations, it is respectfully urged that claims 1 and 3-25 be allowed. Such action is respectfully requested. If the Examiner believes that an interview would be helpful, the Examiner is requested to contact the attorney at the below listed number.

Respectfully Submitted;



Brian S. Steinberger
Registration No. 36,423
101 Brevard Avenue
Cocoa, Florida 32922
Telephone: (321) 633-5080

Date

8/1/07